

WAFER HOLDER FOR SEMICONDUCTOR MANUFACTURING DEVICE AND SEMICONDUCTOR MANUFACTURING DEVICE IN WHICH IT IS INSTALLED

Abstract

Wafer holder for semiconductor manufacturing and semiconductor manufacturing device in which the holder is installed, the wafer holder having a wafer-carrying surface, wherein the isothermal rating of its wafer-carrying surface is enhanced. In the wafer holder having a wafer-carrying surface, by making the diameter a of the wafer holder wafer-carrying surface not greater than the diameter b of the surface on its side opposite the wafer-carrying surface, the temperature distribution superficially in a wafer can be brought to within $\pm 0.5\%$. Moreover, by making $b \leq 50 \text{ } \mu\text{m}$, the temperature distribution can be brought to within $\pm 0.4\%$. The wafer holder is preferably a ceramic susceptor.